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PTO/SB/08A (08-00)

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Substitute for form 1449A/PTO

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary) 26

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Complete if Known

Application Number	09/698,317
Filing Date	October 27, 2000
First Named Inventor	Choi et al.
Group Art Unit	2859
Examiner Name	Unassigned <i>T. Doughty</i>
Attorney Docket Number	PA09-06V02

U.S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

**Examiner
Signature**

Thomas M. Dougherty

Date
Considered

2-12-04

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹Unique citation designation number. ²See attached Kinds of U.S. Patent Documents. ³Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶Applicant is to place a check mark here if English language Translation is attached.

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Substitute for form 1449B/PTO

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Substitute for form 1449B/PTO				Complete if Known	
				PATENT & TRADEMARK	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT				Application Number	09/698,317
(use as many sheets as necessary)				Filing Date	October 27, 2000
				First Named Inventor	Choi et al.
				Group Art Unit	2859
				Examiner Name	Unassigned T. Dwyer
Sheet	2	of	2	Attorney Docket Number	PA09-06V02

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS

OTHER PRIOR ART - NON-PATENT LITERATURE DOCUMENTS				
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.		T ²
TMW	B10	LIN, "Multi-Layer Resist Systems", Introduction of Microlithography", American Chemical Society, 1983, pp. 287-350, IBM T.J. Watson Research Center, Yorktown Heights, New York 10598.		
TMW	B11	COWIE, "Polymers: Chemistry and Physics of Modern Materials", 1991, pp. 408-409, 2 nd Ed, Chapman and Hall, a division of Routledge, Chapman and Hall, Inc., 29 West 35 th Street, NY, NY 10001-2291.		
TMW	B12	CHOU et al., "Imprint of Sub-25 nm Vias and Trenches in Polymers", Applied Physics Letters, November 20, 1995, pp. 3114-3116, vol. 67(21).		
TMW	B13	CHOU et al., "Imprint Lithography with 25-Nanometer Resolution", Science, Apr. 5, 1996, pp. 85-87, vol. 272.		
TMW	B14	CHOU et al., "Imprint Lithography with Sub-10nm Feature Size and High Throughput", Microelectronic Engineering, 1997, pp. 237-240, vol. 35.		
TMW	B15	XIA et al., "Soft Lithography", Agnew. Chem. Int. Ed., 1998, pp. 550-575, vol. 37.		
				TECHNOLOGY CENTER REC'D - 3 MAR 17 2003 RECEIVED TC 1700

Examiner Signature	<i>Thomas M. Dougherty</i>	Date Considered	2-12-04
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¹Inique citation designation number. ²Applicant is to place a check mark here if English language Translation is attached.

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Substitute for form 1449A/PTO

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary)

Sheet

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of

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<i>Complete if Known</i>	
Application Number	09/698,317
Filing Date	October 27, 2000
First Named Inventor	Choi et al.
Group Art Unit	2834
Examiner Name	Dougherty, Thomas M.
Attorney Docket Number	UTS-09-06V02

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¹Unique citation designation number. ²See attached Kinds of U.S. Patent Documents. ³Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶Applicant is to place a check mark here if English language Translation is attached.

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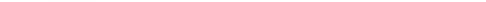
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Substitute for form 1449B/PTO		<i>Complete if Known</i>	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT <small>DEC 21 2003</small> <small>(use as many sheets as necessary)</small>		Application Number	09/698,317
		Filing Date	October 27, 2000
		First Name Inventor	Choi et al.
		Group Art Unit	2834
		Examiner Name	Dougherty, Thomas M.
Sheet	2	of	2
		Attorney Docket Number	
		UTS-09-06V02	

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS

Examiner Signature		Date Considered	Feb. 12, 2004
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¹Unique citation designation number. ²Applicant is to place a check mark here if English language Translation is attached.

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U.S. PATENT AND TRADEMARK OFFICE

Form PTO-1449 (modified) List of Patents and Publications For Applicant's Information Disclosure Statement (Use several sheets if necessary)			ATTY. DKT. NO. 5119-08601 APPLICANT: Choi et al. FILING DATE: October 27, 2000	SERIAL NO. 09/698,317 GROUP: 2859			
U.S. PATENT DOCUMENTS							
EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>JMB</i>	A1	3,807,027	4/1974	Heisler	29	423	
<i>JMB</i>	A2	3,807,029	4/1974	Troeger	29	436	
<i>JMB</i>	A3	3,811,665	5/1974	Seelig	26	RECEIVED	
<i>JMB</i>	A4	4,062,600	12/1977	Wyse	384	285	JUN 26 2002
<i>JMB</i>	A5	4,098,001	7/1978	Watson	33	644	
<i>JMB</i>	A6	4,155,169	5/1979	Drake et al.	33	644	GROUP 3600
<i>JMB</i>	A7	4,202,107	5/1980	Watson	33	644	
<i>JMB</i>	A8	4,267,212	5/1981	Sakawaki	427	240	
<i>JMB</i>	A9	4,337,579	7/1982	De Fazio	33	644	
<i>JMB</i>	A10	4,355,469	10/1982	Nevins et al.	267	150	
<i>JMB</i>	A11	4,414,750	11/1983	De Fazio	267	166	
<i>JMB</i>	A12	4,451,507	5/1984	Beltz et al.	427	240	
<i>JMB</i>	A13	4,610,442	9/1986	Oku et al.	269	73	
<i>JMB</i>	A14	4,694,703	11/1987	Routson	74	5F	
<i>JMB</i>	A15	4,731,155	3/1988	Napoli et al.	216	44	
<i>JMB</i>	A16	4,763,886	8/1988	Takei	269	73	
<i>JMB</i>	A17	4,929,083	5/1990	Brunner	356	400	
<i>JMB</i>	A18	4,959,252	11/1990	Bonnebat et al.	428	64.7	
<i>JMB</i>	A19	5,072,126	12/1991	Progler	250	598	
<i>JMB</i>	A20	5,110,514	5/1992	Soane	264	496	
<i>JMB</i>	A21	5,126,006	6/1992	Cronin et al.	438	702	
<i>JMB</i>	A22	5,204,739	4/1993	Domenicali	348	79	
<i>JMB</i>	A23	5,240,550	8/1993	Boehnke et al.	216	24	
<i>JMB</i>	A24	5,348,616	9/1994	Hartman et al.	216	48	
<i>JMB</i>	A25	5,392,123	2/1995	Marcus et al.	356	625	
<i>JMB</i>	A26	5,425,964	6/1995	Southwell et al.	427	10	
<i>JMB</i>	A27	5,452,090	9/1995	Progler et al.	356	401	

EXAMINER: *Thomas M. Kugelby* DATE CONSIDERED: *Feb. 13, 2009*

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Form PTO-1449 (modified) List of Patents and Publications For Applicant's Information Disclosure Statement JUN 21 2002 (Use several sheets if necessary)		ATTY. DKT. NO. 5119-08601 APPLICANT: Choi et al. FILING DATE: October 27, 2000	SERIAL NO. 09/698,317 GROUP: 2859
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U.S. PATENT DOCUMENTS

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
TmD	A28	5,480,047	1/1996	Tanigawa et al.	216	12	
TmD	A29	5,512,131	4/1996	Kumar et al.	438	RECEIVED	
TmD	A30	5,515,167	5/1996	Ledger et al.	356	595	JUN 26 2002
TmD	A31	5,545,367	10/1996	Bae et al.	261	481	
TmD	A32	5,566,584	10/1996	Briganti et al.	74	900,074	GROUP 3600
TmD	A33	5,633,505	5/1997	Chung et al.	250	491.1	
TmD	A34	5,724,145	3/1998	Kondo et al.	356	632	
TmD	A35	5,753,014	5/1998	Van Rijn	96	12	
TmD	A36	5,760,500	6/1998	Kondo et al.	310	12	
TmD	A37	5,772,905	6/1998	Chou	216	44	
TmD	A38	5,776,748	7/1998	Singhvi et al.	435	180	
TmD	A39	5,779,799	7/1998	Davis	118	663	
TmD	A40	5,802,914	9/1998	Fassler et al.	74	110	
TmD	A41	5,877,036	3/1999	Kawai	438	16	
TmD	A42	5,877,861	3/1999	Ausschnitt et al.	356	401	
TmD	A43	5,888,650	3/1999	Calhoun et al.	426	354	
TmD	A44	5,900,160	5/1999	Whitesides et al.	216	41	
TmD	A45	5,912,049	6/1999	Shirley	427	240	
TmD	A46	5,942,871	8/1999	Lee	318	611	
TmD	A47	5,948,470	9/1999	Harrison et al.	427	148	
TmD	A48	5,952,127	9/1999	Yamanaka	430	5	
TmD	A49	6,038,280	3/2000	Rossiger et al.	378	50	
TmD	A50	6,039,897	3/2000	Lochhead et al.	264	1,24	
TmD	A51	6,046,056	4/2000	Parce et al.	204	409.05	
TmD	A52	6,051,345	4/2000	Huang	430	5	
TmD	A53	6,074,827	6/2000	Nelson et al.	435	6	
TmD	A54	6,091,485	7/2000	Li et al.	356	73	
	A55	6,128,085	10/2000	Buermann et al.	356	369	

EXAMINER:

Thomas M. Rappleye

DATE CONSIDERED:

Feb. 13, 2004

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Form PTO-1449 (modified)		ATTY. DKT. NO. 5119-08601	SERIAL NO. 09/698,317
List of Patents and Publications For Applicant's Information Disclosure Statement (Use several sheets if necessary)		APPLICANT: Choi et al. FILING DATE: October 27, 2000	GROUP: 2859

U.S. PATENT DOCUMENTS

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
JMD	A56	6,143,412	11/2000	Schueller et al.	428	408	RECEIVED
JM	A57	6,168,845	1/2001	Fontana, Jr. et al.	428	65,5	
JMD	A58	6,180,239	1/2001	Whitesides et al.	428	411	JUN 26 2002
JMD	A59	6,204,922	3/2001	Chalmers	356	731	GROUP 3600
JM	A60	6,334,960	1/2002	Wilson et al.	216	52	

FOREIGN PATENT DOCUMENTS

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES/NO
JMD	A61	00/54107	9/2000	WO	608F	7/08	
JMD	A62	01/33232	5/2001	WO	601R	—	
JMD	A63	01/33300	5/2001	WO	402K	5/24	
JM	A64	244884	3/1987	EP	829C	33/34	
JM	A65	733455	9/1996	EP	829C	33/34	NO
JMD	A66	2800476	7/1978	DE	603C	5/08	NO
JMD	A67	19648844	11/1999	DE	829C	59/02	NO
JMD	A68	1-196749	8/1989	JP	611B	7/26	NO

EXAMINER: Thomas M. DoughertyDATE CONSIDERED: Feb. 13, 2004

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OTHER ARTICLES (Including Author, Title, Date, Pertinent Pages, Etc.)				
	A69	Stewart, D.; "A Platform with Six Degrees of Freedom", Proc. of Inst. Mech. Engrs., 1965, 180, 371-378.		
	A70	Paros, J.M.; Weisbord, L.; "How to Design Flexure Hinges", Machine Design, 1965, 151-156.		
	A71	Raibert, M.H.; Craig, J.J.; "Hybrid Position/Force Control of Manipulators", 1981, 102, 126-133.		
	A72	Hogan, Neville; "Impedance Control: An Approach to Manipulation", Journal of Dynamic Systems, Measurement and Control, 1985, 107, 1-7.		
	A73	Hollis, Ralph; Salvendy, S.E.; Allan, A.P.; "A Six-Degree-of-Freedom Magnetically Levitated Variable Compliance Fine-Motion Wrist: Design, Modeling and Control", IEEE Transactions on Robotics and Automation, 1991, 7, 320-332.		
	A74	Tomita, Y. et al.; "6-Axes Motion Control Method for Parallel-Linkage-Type Fine Motion Stage", Journal of Japan Society of Precision Engineering, 1992, 118-124.		
	A75	Slocum, Alexander; "Precision Machine Design: Macromachine Design Philosophy and its Applicability to the Design of Micromachines", Proc. of IEEE Micro Electro Mech. Systems Workshop, 1992, 37-42.		
	A76	Krug, Herbert; Merl, Norbert; Schmidt, Helmut; "Fine Patterning of Thin Sol-Gel Films", Journal of Non-Crystalline Solids, 1992, 447-450.		
	A77	Arai, T.; Laronneur, R.; Jaya, Y.M.; "Calibration and Basic Motion of a Micro Hand Module", Proc. of IECON, 1993, 1660-1665.		
	A78	Peng, Zhi-Xin; Adachi, N.; "Compliant Motion Control of Kinematically Redundant Manipulators", IEEE Transactions on Robotics and Automation, 1993, 9, 831-837.		
	A79	Rong, Y.; Zhu, Y.; Luo, Z.; Liu, X.; "Design and Analysis of Flexure-Hinge Mechanism Used in Micro-Positioning Stages", ASME, 1994, 2, 979-985.		
	A80	Hashimoto, M.; Imamura, Y.; "Design and Characteristics of a Parallel Link Compliant Wrist", IEEE International Conference on Robotics and Automation, 1994, 2457-2462.		
	A81	Merlet, J.P.; "Parallel Manipulators: State of the Art and Perspectives", Advanced Robotics, 1994, 8, 589-596.		
	A82	Ananthasuresh, S.; Kikuchi, N.; "Strategies for Systematic Synthesis of Compliant MEMS", ASME, 1994, 2, 677-686.		
	A83	Arai, T.; Tanikawa, T.; Merlet, J.P.; Sendai, T., "Development of a New Parallel Manipulator with Fixed Linear Actuator", Proc. of Japan/USA Symposium on Flexible Automation, 1996, 1, 145-149.		
	A84	Howell, L.L.; Midha, A.; "Loop-Closure Theory of the Analysis and Synthesis of Compliant Mechanisms", Journal of Mechanical Design, 1996, 118, 121-125.		
	A85	Haisma, J. et al.; "Mold-Assisted Nanolithography: A Process for Reliable Pattern Replication", Journal of Vacuum Science and Technology, 1996, 14, 4124-4128.		
	A86	Pernette, Eric; Henein, Simon; Magnani, Ivo; Clavel, Reymond; "Design of Parallel Robots in Microrobotics", Robotica, 1997, 15, 417-420.		

EXAMINER:

DATE CONSIDERED:

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GROUP 2859
GROUP 3600

Form PTO-1449 (modified)		ATTY. DKT. NO. 5119-08601	Serial No. 09/698,317
List of Patents and Publications			
For Applicant's Information JUN 21 2002			
Disclosure Statement			
(Use several sheets if necessary)			
Tony	A87	Rong, L.; Guang, H.; "Dynamics of Parallel Mechanism with Direct Compliance Control", IEEE, 1997, 1753-1758.	
Tony	A88	Mittal, Samir; Menq, Chia-Hsiang; "Precision Motion Control of Magnetic Suspension Actuator Using a Robust Nonlinear Compensation Scheme", IEEE/ASME Transactions on Mechatronics, 1997, 2, 268-280.	
Tony	A89	Physik Instruments, Product Catalog for Micropositioning, 1997.	
Tony	A90	Williams, Mark et al.; "Six Degree of Freedom Mag-Lev Stage Development", SPIE, 1997, 3051, 856-867.	
Tony	A91	Lee, Chang-Woo; Kim, Seung-Woo; "Ultraprecision Stage for Alignment of Wafers in Advanced Microlithography", Precision Engineering, 1997, 21, 113-122.	
Tony	A92	Kanetomo, M.; Kashima, H.; Suzuki, T.; "Robot for Use in Ultrahigh Vacuum", Solid State Tech., 1997, 63-72.	
Tony	A93	Goldfarb, M.; Speich, J.; "Compliant Micromanipulator Design for Scaled Bilateral Telemanipulation of Small-Scale Environments", ASME, Dynamic Systems and Control Div., 1998, 64, 213-218.	
Tony	A94	Koseki, Y. et al.; "Design and Accuracy Evaluation of High-Speed and High Precision Parallel Mechanism", Proc. of IEEE, Intl. Conf. on Robotics & Automation, 1998, 1340-1345.	
Tony	A95	Kim, Won-Jong; Trumper, David; "High Precision Magnetic Levitation Stage for Photolithography", Precision Engineering, 1998, 22, 66-77.	
Tony	A96	Mansky, P. et al.; "Large-Area Domain Alignment in Block Copolymer Thin Films Using Electric Fields", Macromolecules, 1998, 31, 4399-4401.	
Tony	A97	Wang, W.; Loh, R.; Gu, E.; "Passive Compliance Versus Active Compliance in Robot-Based Automated Assembly Systems", Industrial Robot, 1998, 25, 48-57.	
Tony	A98	Scheer, H.C. et al.; "Problems of Nanoimprinting Technique for Nanometer Scale Pattern Definition", Journal of Vacuum Science and Technology, 1998, 16, 3917-3921.	
Tony	A99	Xia, Y.; Whitesides, George; "Soft Lithography", Annu. Rev. Mater. Sci., 1998, 28, 153-184.	
Tony	A100	Tajbakhsh, H. et al.; "Three-Degree-of-Freedom Optic Mount for Extreme Ultraviolet Lithography", ASPE, 1998, 18, 359-362.	
Tony	A101	Lee, Dong Sung et al.; "Ultra Precision Positioning System for Servo Motor-Piezo Actuator Using Dual Servo Loop and Digital Filter Implementation", ASPE, 1998, 18, 287-290.	
Tony	A102	Wu, Wei et al.; "Large Area High Density Quantized Magnetic Disks Fabricated Using Nanoimprint Lithography", 1998, Journal of Vacuum Science and Technology, 1998, 16, 3825-3829.	
Tony	A103	Ohya, Y. et al.; "Development of 3-DOF Finger Module for Micro Manipulation", Proc. of IEEE, Intl. Conf. on Intelligent Robots and Systems, 1999, 894-899.	
Tony	A104	Tanikawa, T. et al.; "Development of Small-Sized 3 DOF Finger Module in Micro Hand for Micro Manipulation", Proc. of IEEE, Intl. Conf. on Intelligent Robots and Systems, 1999, 876-881.	
Tony	A105	Colburn, M. et al.; "Step and Flash Imprint Lithography: New Approach to High-Resolution Patterning", Proc. of SPIE, 1999, 3676, 379-389.	

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DATE CONSIDERED:

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List of Patents and Publications For Applicant's Information Disclosure Statement (Use several sheets if necessary)		APPLICANT: Choi et al.	GROUP: 2859
		FILING DATE: October 27, 2002	JUN 26 2002
<i>Dmn</i>	A106	RECEIVED GROUP 3600	
<i>Tmb</i>	A107	Goldfarb, M.; Speich, J.E.; "A Well-Behaved Revolute Flexure Joint for Compliant Mechanism Design", Journal of Mech. Design, 1999, 121, 424-429.	
<i>Tmb</i>	A108	Geodetic Technology, G1000-PS Power Series Specifications, 1999, from www.hexapods.com	
<i>Tmb</i>	A109	Hexel Corporation, Tornado 2000 System Specifications, 1999, from www.hexel.com	
<i>Tmb</i>	A110	Physik Instruments, PI Online-Catalog, 1999, from www.physikinstruments.com	
<i>Tmb</i>	A111	Chou, Stephen; Zhuang, Lei; "Lithographically-induced Self Assembly of Periodic Micropillar Arrays", Journal of Vacuum Science and Technology, 1999, 17, 3197-3202.	
<i>MWD</i>	A112	Ruchhoeft, P. et al.; "Patterning Curved Surfaces: Template Generation by Ion Beam Proximity Lithography and Relief Transfer by Step and Flash Imprint Lithography", Journal of Vacuum Science and Technology, 1999, 17, 2965-2982.	
<i>MWD</i>	A113	Vanderbilt University Office of Transfer Technology; VU 9730 Specifications for Improved Flexure Device; 2001, from www.vanderbilt.edu	
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EXAMINER: *Thomas M. Connelly* DATE CONSIDERED: *Feb. 13, 2004*

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